

## Supplementary Information

# Van der Waals interaction-induced photoluminescence weakening and multilayer growth in epitaxially aligned WS<sub>2</sub>

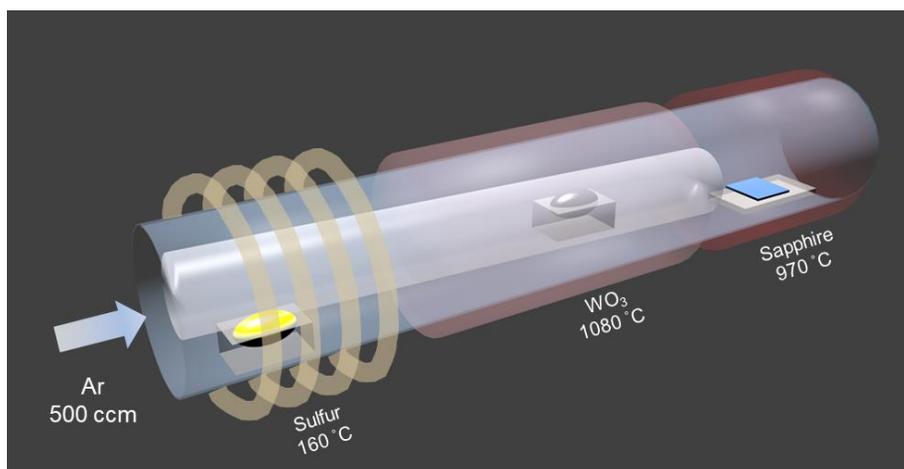
Hyun Goo Ji,<sup>a</sup> Mina Maruyama,<sup>b</sup> Adha Sukma Aji,<sup>a</sup> Susumu Okada,<sup>b</sup> Kazunari Matsuda,<sup>c</sup> and Hiroki Ago<sup>a,d,\*</sup>

<sup>a</sup> *Interdisciplinary Graduate School of Engineering Sciences, Kyushu University, Fukuoka 816-8580, Japan*

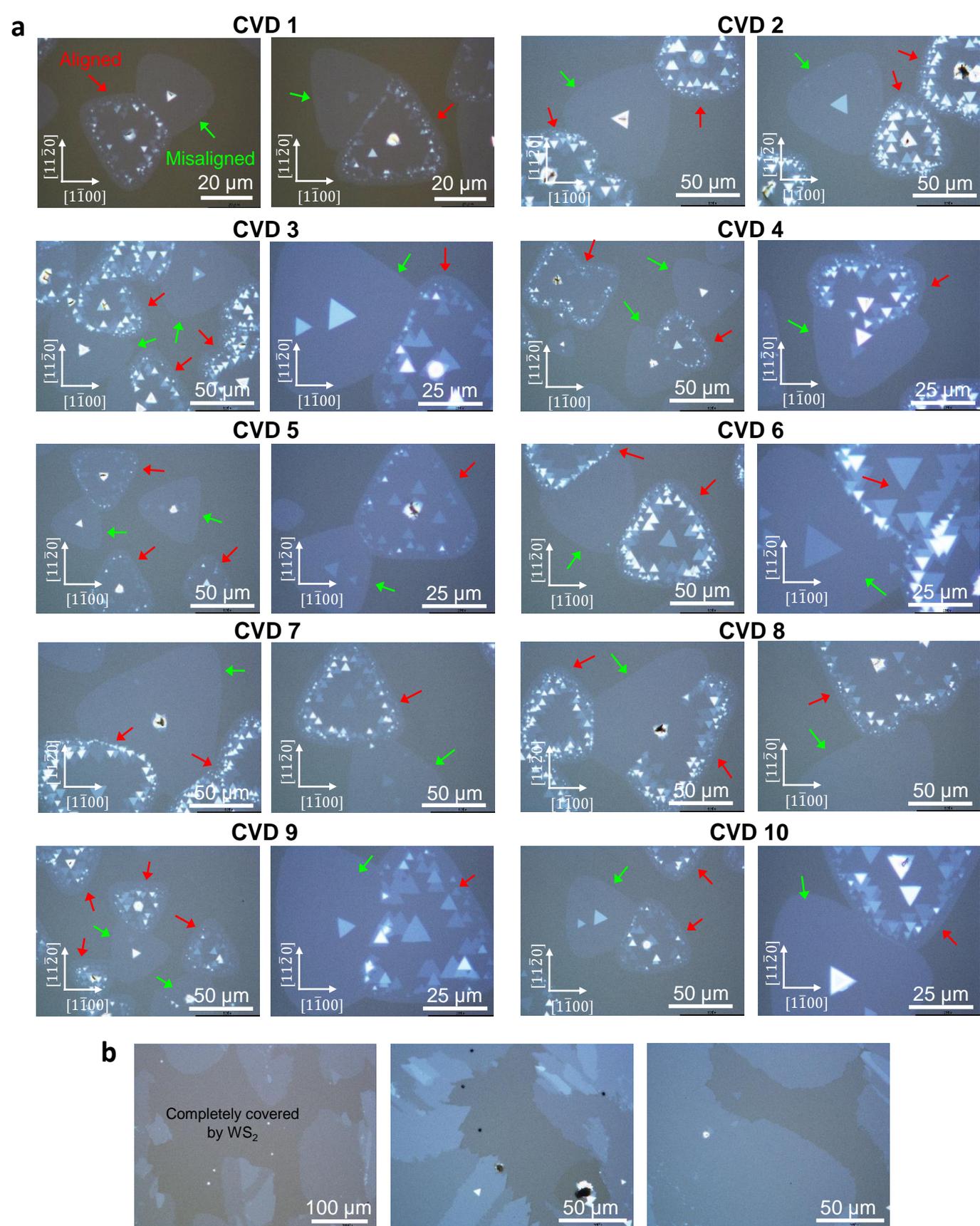
<sup>b</sup> *Graduate School of Pure and Applied Sciences, University of Tsukuba, Ibaraki 305-8571, Japan*

<sup>c</sup> *Institute of Advanced Energy, Kyoto University, Uji, Kyoto, 611-0011, Japan*

<sup>d</sup> *Global Innovation Center (GIC), Kyushu University, Fukuoka 816-8580, Japan*



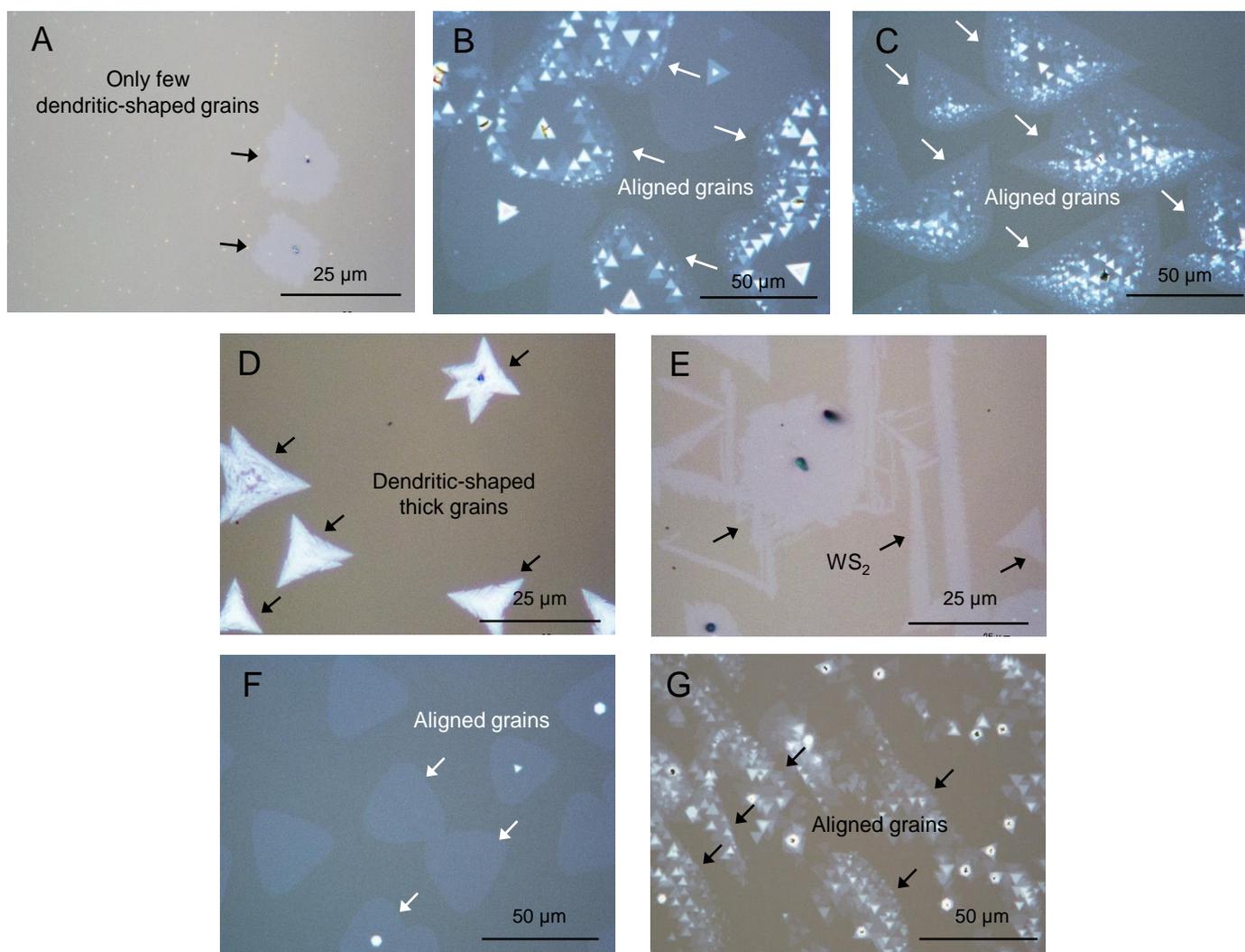
**Figure S1.** CVD condition used for WS<sub>2</sub> growth on sapphire.



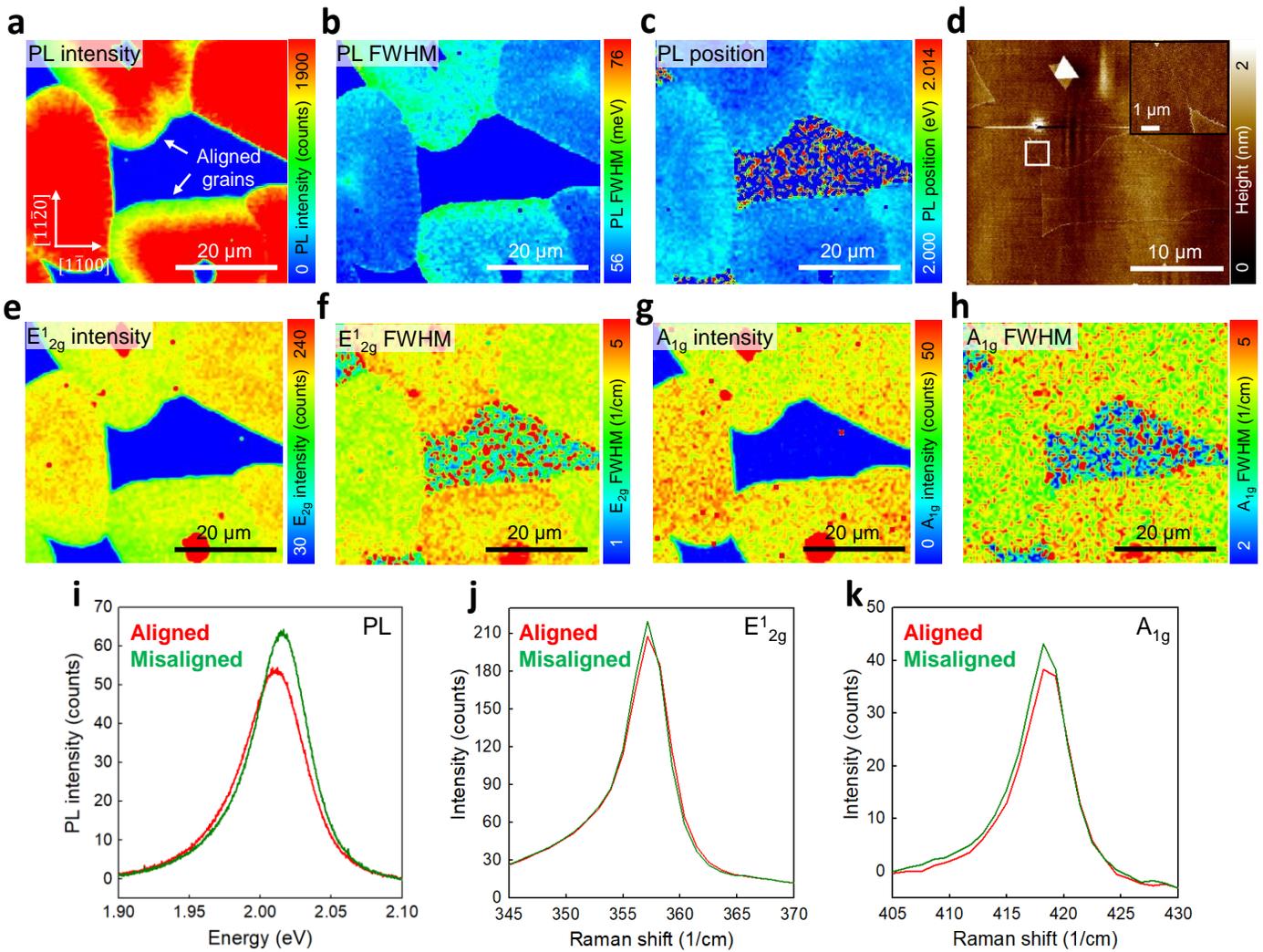
**Figure S2.** Optical micrographs of as-grown  $\text{WS}_2$  grains on sapphire substrates. (a) The preferential overlayer deposition was observed on the aligned grains. (b) In a few cases, the sapphire surface was fully covered with  $\text{WS}_2$  together with large multilayer grains.

**Table S1.** CVD conditions used for sample (A) ~ (G) shown in Figure S3 and the observed growth modes.

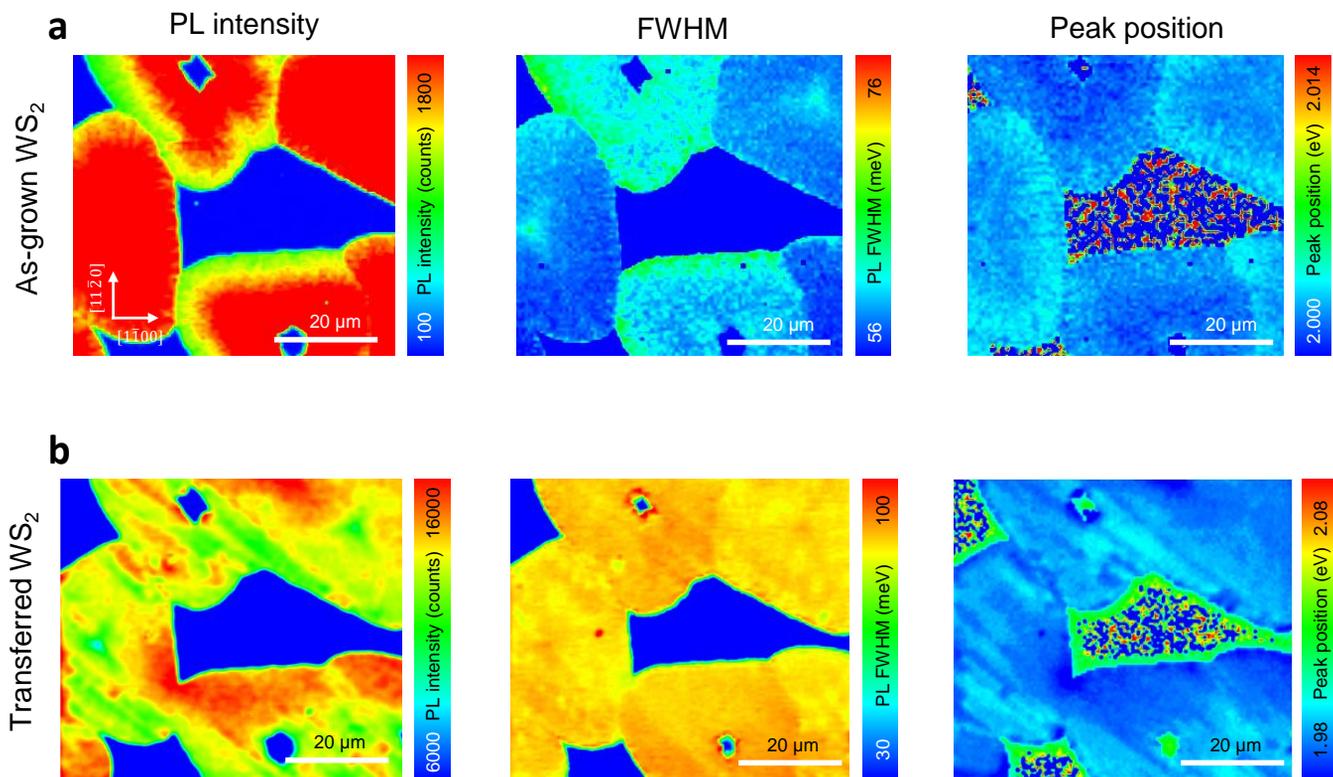
	Growth parameters				Growth mode	
	Gas flow rate	WO <sub>3</sub>	S	sapphire	Epitaxially aligned grains	Preferential multilayer growth
A	300 ccm	1080 °C	160 °C	970 °C	X	X
B	500 ccm				O	O
C	700 ccm				O	O
D	500 ccm	1075 °C	160 °C	770 °C	X	X
E				870 °C	X	X
F				970 °C	O	X
G				1070 °C	O	O



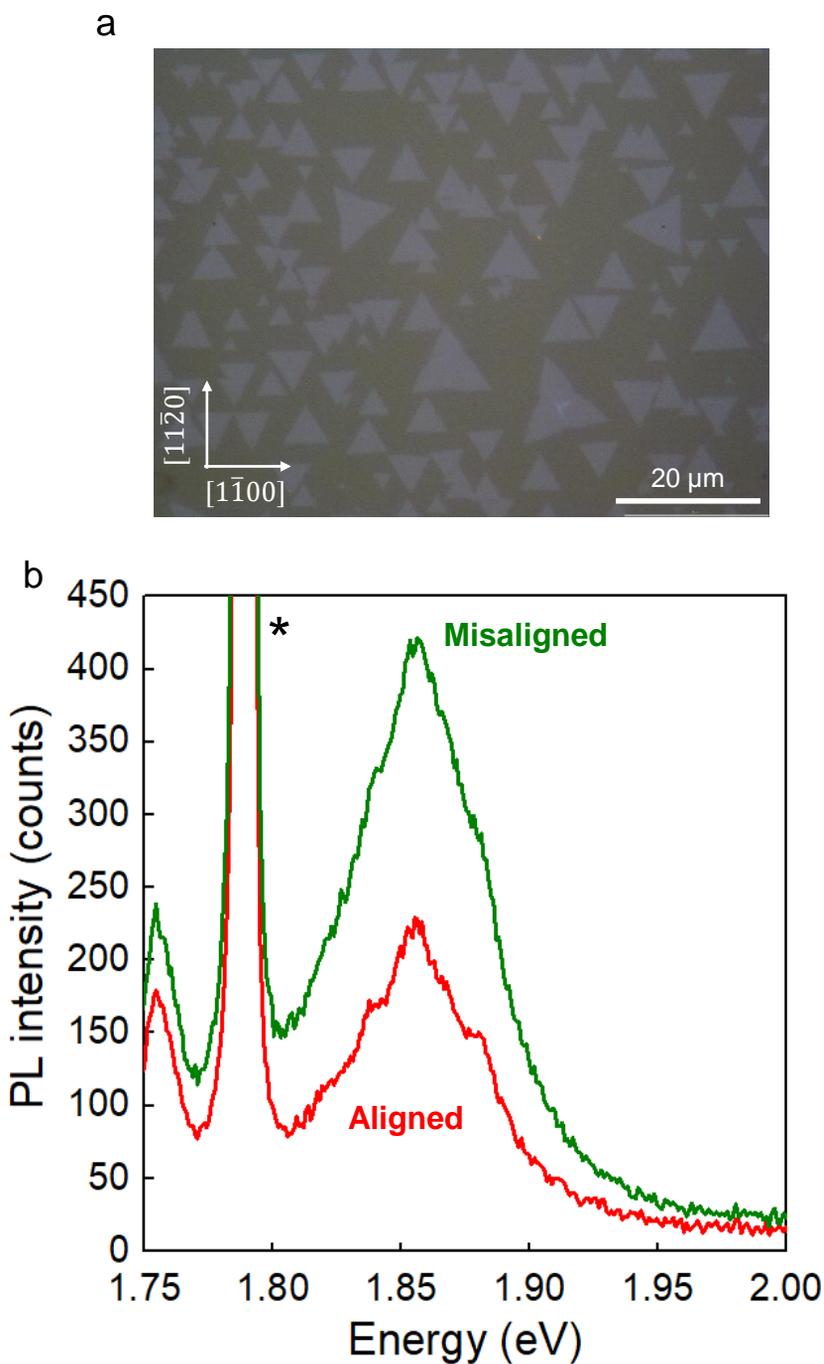
**Figure S3.** Optical images of as-grown WS<sub>2</sub> on c-plane sapphire synthesized using the growth conditions shown in Table S1.



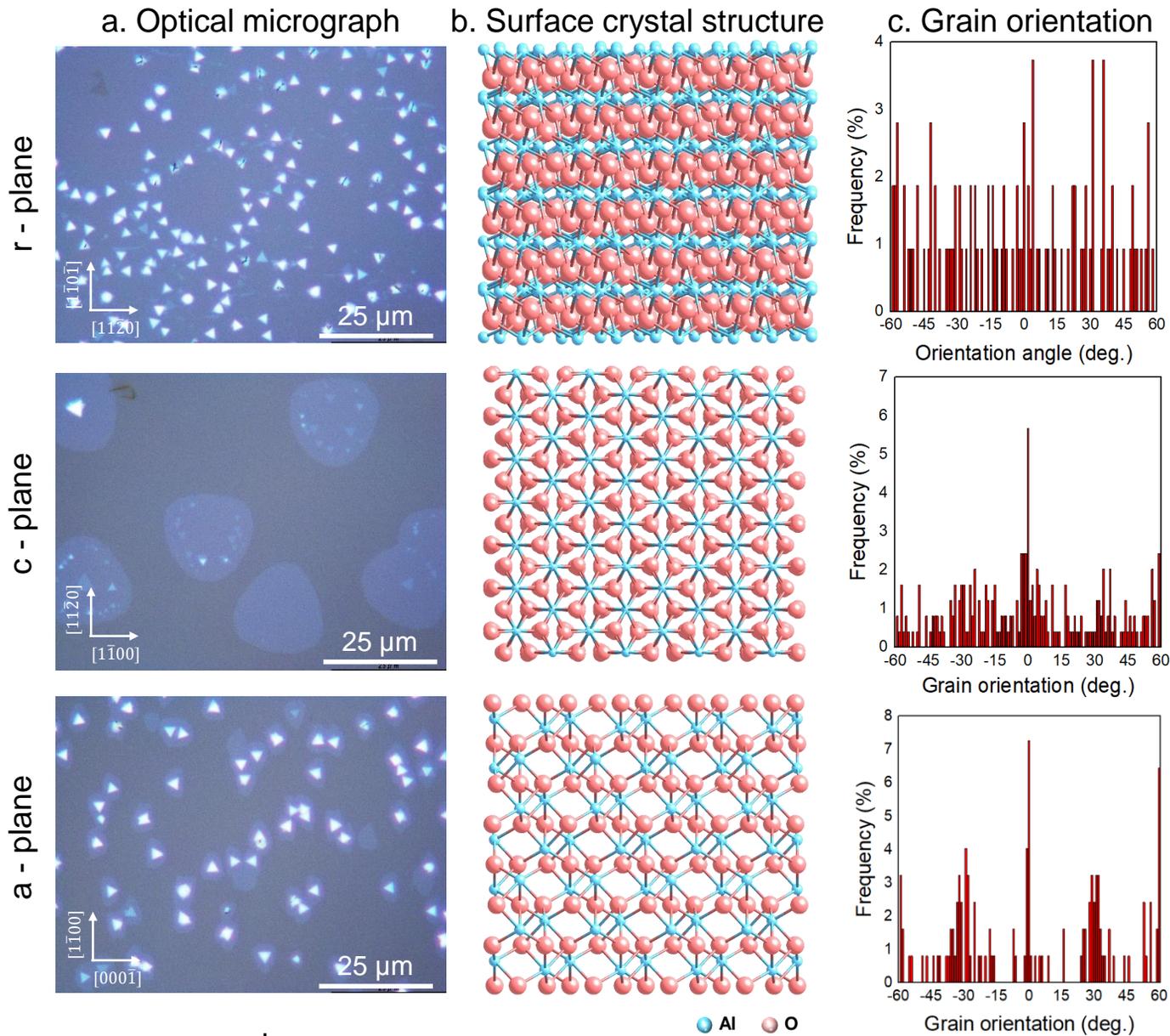
**Figure S4.** PL mapping images of the peak intensity (a), FWHM (b), and position (c) of monolayer WS<sub>2</sub> grains. (d) AFM height image. The inset shows a magnified image of the marked area. Raman E<sub>12g</sub> mappings with intensity (e) and FWHM (f), and A<sub>1g</sub> mappings with intensity (g) and FWHM (h). (i) PL, (j) E<sub>12g</sub>, and (k) A<sub>1g</sub> spectra taken from as-grown aligned and misaligned grains.



**Figure S5.** PL mapping images of identical WS<sub>2</sub> grains before (a) and after (b) transfer on SiO<sub>2</sub>/Si substrate. The difference in PL intensity observed between aligned- and misaligned-grains in as-grown WS<sub>2</sub> disappeared after the transfer process. The wavy patterns observed in the PL intensity of the transferred WS<sub>2</sub> (b) are from wrinkles induced during transfer process.



**Figure S6.** OM image and PL spectra of MoS<sub>2</sub> grown on c-plane sapphire. In the OM image (a), oriented grains are aligned along [1 $\bar{1}$ 00] axis of sapphire substrate. PL spectra are shown in (b) where red and green spectra correspond to PL from aligned- and misaligned-grains, respectively. Asterisk (\*) indicates a peak from a sapphire substrate. The peak at ~1.76 eV corresponds to bound exciton in MoS<sub>2</sub>.



**Figure S7.** (a) OM images of CVD-grown WS<sub>2</sub> on different planes of sapphire substrates. (b) Surface crystal structure of each sapphire plane. (c) Grain orientation histogram of WS<sub>2</sub> grown on each sapphire plane. [11 $\bar{2}$ 0], [1 $\bar{1}$ 00], and [000 $\bar{1}$ ] axes are set as 0° for r-, c-, and a-plane sapphire, respectively. (d) PL spectra from the as-grown WS<sub>2</sub> grains.